

METHODS AND APPARATUS FOR INSPECTING CONTACT OPENINGS IN A PLASMA PROCESSING SYSTEM

ABSTRACT

In a plasma processing system, a method of inspecting a contact opening of a contact formed in a first layer of the substrate to determine whether the contact reaches a metal layer that is disposed below the first layer is shown. The method includes flowing a gas mixture into a plasma reactor of the plasma processing system, the gas mixture comprising a flow of a chlorine containing gas. The method also includes striking a plasma from the gas mixture; and exposing the contact to the plasma. The method further includes detecting whether metal chloride is present is the contact after the exposing.